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## HEIQ & ODLO TO LAUNCH HEIQ PURE SPQR AT PERFORMANCE DAYS



Courtesy: HeiQ

HeiQ and Odlo, Swiss developers of functional clothing, are co-launching HeiQ Pure SPQR, a triple-action sustainable odour control technology, another breakthrough in the HeiQ Fresh Tech product family, at the Performance Days expo, in booth 05, workshop room P07. The functional fabrics expo will be held on November 28 and 29, 2018, in Munich, Germany.

For the past three years, HeiQ and Odlo spent thousands of hours in the laboratory and in the field to develop HeiQ Pure SPQR, which is the latest breakthrough in the HeiQ Fresh Tech product family and will be engineered into Odlo's Spring/Summer'2020 next-to-skin products, according to HeiQ.

HeiQ Pure SPQR is derived from renewable and recycled sources, and delivers a triple-action for an unprecedented odour control efficiency: first, with only one-tenth of silver-ion content as compared to general silver-based odour control treatments, it is able to effectively impair the metabolism of bacteria (the process that turns odourless sweat into body odour). This is due to the second action – bio-based amino sugar polymer anchors silver-ions to amplify their performance and durability. And third, at a microscopic level, the amino sugar polymer creates a durable barrier film around the fibre, preventing odour compounds from sticking on the textile. Thus, garments can be washed easily at low temperature, which extends the usable life of the garment and is more sustainable.

“It’s with great pride that we fulfil our promise to our late mentor Odd Lofteroed Jr. to never give up and never be content with the status quo. Once again, with Odlo, we are one step ahead of our competitors in providing a better and more sustainable odour control solution,” Carlo Centonze, co-founder and CEO of HeiQ said. (GK)